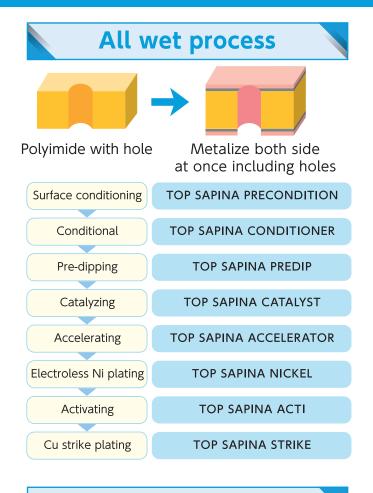
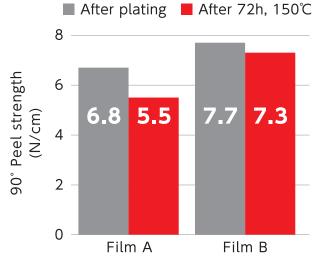
TOP SAPINA PROCESS

Ni seed layer forming process to polyimide film with hole



Great adhesion and stability after aging



Comparison of peel strength (Cu thickness:12µm)

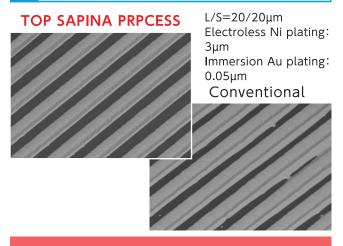
Low Pd concentration Prevent Pd adsorption

Comparison of Pd concentration and adsorption amount

	Pd concentration in catalyst (mg/l)	Pd adsorption amount (µg/dm²)
TOP SAPINA PROCESS (Alkaline ion type)	105	17
Conventional (Acid colloid type)	190	30

Low Pd concentration, eco-friendly process

Excellent in fine pattern performance



Great fine pattern ability of Ni/Au plating because of low Pd adsorption amount